



Lattice Platform Manager 2 Product Family Qualification Summary

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1.0 INTRODUCTION

The Lattice Platform Manager 2 device is a fast-reacting, programmable logic-based Hardware Management Controller. Platform Manager 2 is an integrated solution combining analog sense and control elements with scalable programmable logic resources.

The L-ASC10 (Analog Sense and Control - 10 rail also referred to as ASC) is a Hardware Management Expander designed to be used with Platform Manager 2 or MachXO2 FPGAs to implement the Hardware Management Control function in a circuit board.

Table 1.01 Platform Manager 2 Family

	H/W Management Expander	Hardware Management Controller		
	L-ASC10	LPTM20	LPTM21	LPTM21L
Voltage Monitoring Inputs	10	8	10	
Current Monitoring Inputs	2	2	2	
Temperature Monitoring Inputs	2	2	2	
Number of Trimming Channels	4	2	4	
MOSFET Drives	4	4	4	
On-Chip Non-Volatile Fault Log	✓	✓	✓	
Number of LUTs	-	640	1280	
Distributed RAM (Kbits)	-	5	10	
EBR SRAM (kBits)	-	18	64	
Number of EBR Blocks (9 kBits)	-	2	7	
User Flash Memory (kBits)	-	24	64	
Number of PLLs	-	0	1	
Communication I/F	I2C	I2C/SPI/JTA		
Programming Interface	I2C	I2C/SPI/JTA		
Operating Voltage	3.3	I2C/SPI/JTA		
Insystem Update Support	Yes			
Package Options	Digital I/Os			
48-pin QFN (7mmx7mm)	9			
128-pin TQFP (14mmx14mm)		60		
237-ball ftBGA (17mmx17mm)			95	
100-ball caBGA (10mmx10mm)				32

2.0 LATTICE PRODUCT QUALIFICATION PROGRAM

Lattice Semiconductor Corp. maintains a comprehensive reliability qualification program to assure that each product achieves its reliability goals. After initial qualification, the continued high reliability of Lattice products is assured through ongoing monitor programs as described in Reliability Monitor Program Procedure (Doc. #101667). All product qualification plans are generated in conformance with Lattice Semiconductor's Qualification Procedure (Doc. #100164) with failure analysis performed in conformance with Lattice Semiconductor's Failure Analysis Procedure (Doc. #100166). Both documents are referenced in Lattice Semiconductor's Quality Assurance Manual, which can be obtained upon request from a Lattice Semiconductor sales office or downloaded from the lattice website at www.latticesemi.com. Figure 2.1 shows the Product Qualification Process Flow.

If failures occur during qualification, an 8-Discipline (8D) process is used to find root cause and eliminate the failure mode from the design, materials, or process. The effectiveness of any fix or change is validated through additional testing as required. Final testing results are reported in the qualification reports.

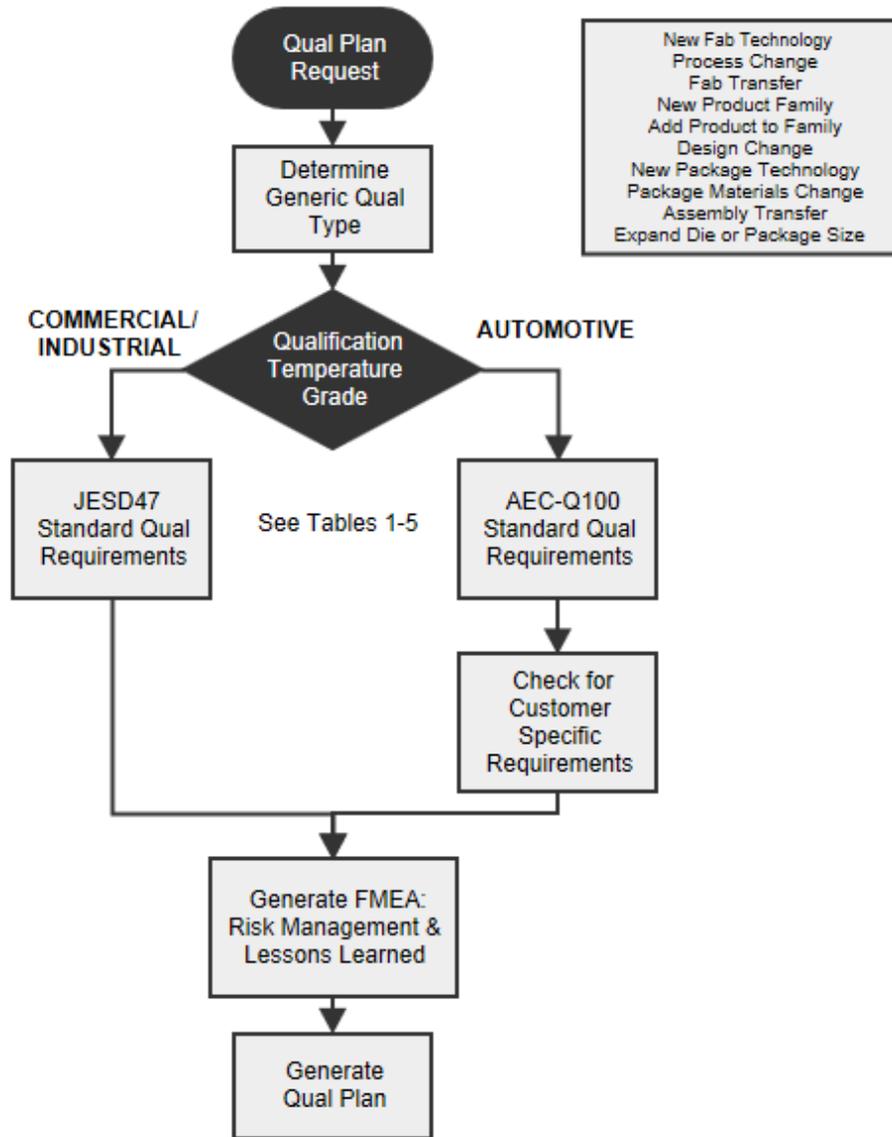
Failure rates in this reliability report are expressed in FITS. Due to the very low failure rate of integrated circuits, it is convenient to refer to failures in a population during a period of 10^9 device hours; one failure in 10^9 device hours is defined as one FIT.

Product families are qualified based upon the requirements outlined in Table 2.2. In general, Lattice Semiconductor follows the current Joint Electron Device Engineering Council (JEDEC) and Military Standard testing methods. Lattice automotive products are qualified and characterized to the Automotive Electronics Council (AEC) testing requirements and methods. Product family qualification will include products with a wide range of circuit densities, package types, and package lead counts. Major changes to products, processes, or vendors require additional qualification before implementation.

Lattice Semiconductor maintains a regular reliability monitor program. The current Lattice Reliability Monitor Report can be found at [Product Reliability Monitor Report](#).

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Figure 2.01 Platform Manager 2 Product Qualification Process Flow



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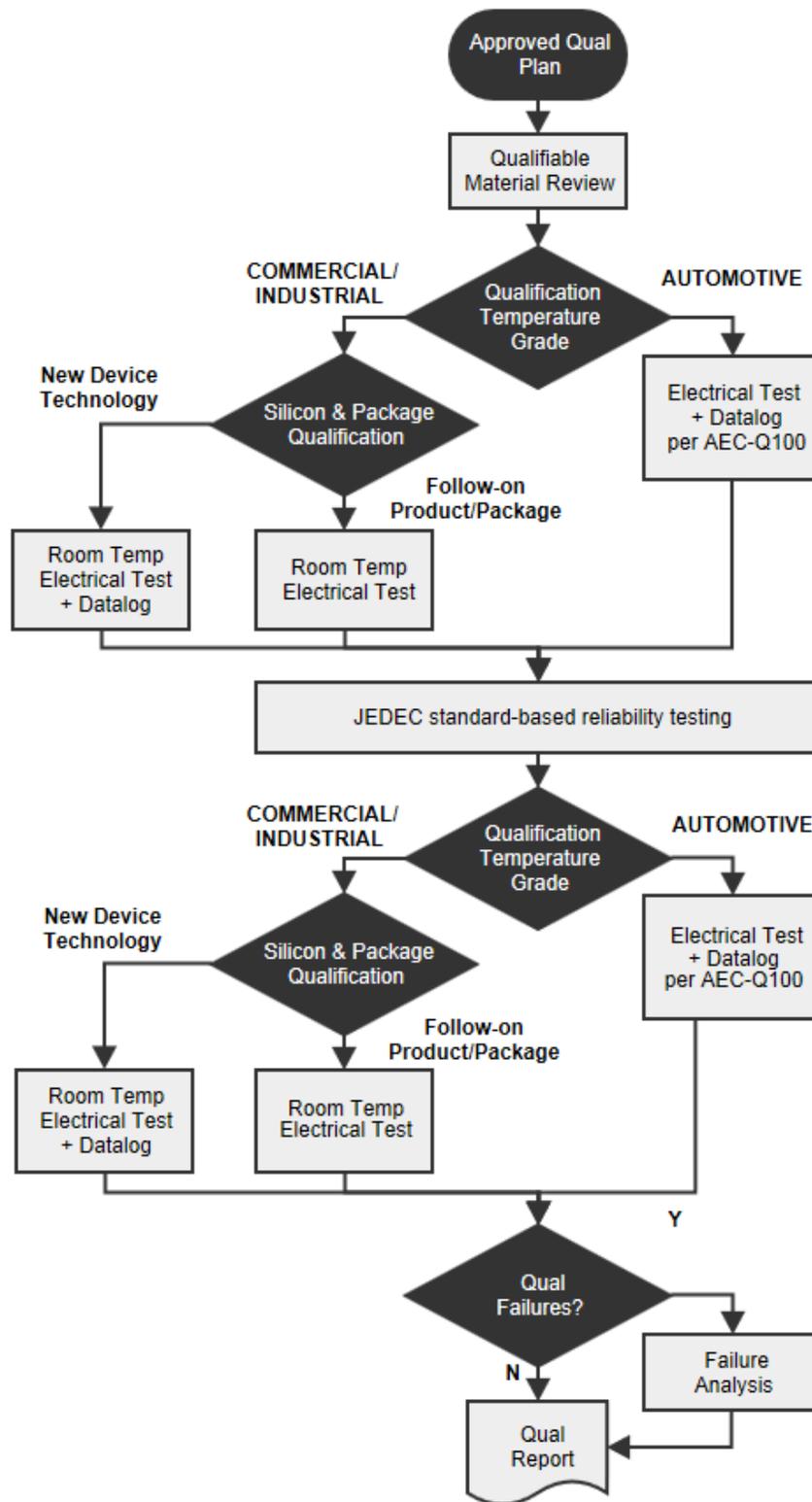


Table 2.02 Standard Qualification Testing

TEST	STANDARD	TEST CONDITIONS	SAMPLE SIZE (Typical)	PERFORMED ON
High Temperature Operating Life HTOL	MIL-STD-883, Method 1005.8, JESD22-A108	125°C, Maximum operating Vcc, 168, 500, 1000, 2000 hrs.	77/lot 2-3 lots	Design, Foundry Process, Package Qualification
Low Temperature Operating Life LTOL	JESD22-A108	-40°C Maximum operating Vcc, 168, 500, 1000 hrs.	77/lot 1 lot	Design, Foundry Process, Package Qualification
High Temp Storage Life HTSL	JESD22-A103	150°C, at 168, 500, 1000, 2000 hours.	77/lot 2-3 lots	Design, Foundry Process, Package Qualification
ESD HBM	MIL-STD-883, Method 3015.7, JS-001-2014	Human Body Model	3 parts/lot 1-3 lots typical	Design, Foundry Process
ESD CDM	JS-002-2014	Charged Device model	3 parts/lot 1-2 lots typical	Design, Foundry Process
Latch Up Resistance LU	JESD78	±100 ma on I/O's, Vcc +50% on Power Supplies. (Max operating temp.)	6 parts/lot 1-2 lots typical	Design, Foundry Process
Surface Mount Pre- conditioning SMPC	IPC/JEDEC J-STD-020D.1 JESD-A113 FPGA - MSL 3	5 Temp cycles, 24 hr 125°C Bake 192hr. 30/60 Soak 3 SMT simulation cycles	All units going into Temp Cycling, UHAST, BHAST, 85/85	Plastic Packages only
Temperature Cycling TC	MIL-STD- 883, Method 1010, Condition B JESD22-A104	(700 cycles) Repeatedly cycled between -55°C and +125°C in an air environment	77 parts/lot 2-3 lots	Design, Foundry Process, Package Qualification
Unbiased HAST UHAST	JESD22-A118	2 atm. Pressure, 96 hrs/130C (TQFP, QFN) 264 hrs/110C (BGA) 85% Relative Humidity	77 parts/lot 2-3 lots	Foundry Process, Package Qualification Plastic Packages only
Moisture Resistance Temperature Humidity Bias 85/85 THBS or Biased HAST BHAST	JESD22-A101 JESD22-A110	Biased to maximum operating Vcc, 85°C, 85% Relative Humidity, 1000 hours or Biased to maximum operating Vcc, 2atm. Pressure, 96 hrs/130°C (TQFP, QFN) 264 hrs/110°C (BGA) 85% Relative Humidity	77 devices/lot 2-3 lots	Design, Foundry Process, Package Qualification Plastic Packages only

TEST	STANDARD	TEST CONDITIONS	SAMPLE SIZE (Typical)	PERFORMED ON
Physical Dimensions	MIL-STD- 883 Method 2016 or applicable LSC case outline drawings	Measure all dimensions listed on the case outline.	5 devices	Package Qualification
Ball Shear	JESD22-B117	Per Package Type	3 devices per package / 30 balls each unit	Package Qualification

3.0 SILICON QUALIFICATION DATA FOR THE PLATFORM MANAGER 2 PRODUCT FAMILY

The Platform Manager 2 product family combines two proven die solutions assembled into both a stacked die TQFP and a multi-chip module ftBGA package configurations. The Analog section of the Platform Manager 2 is comprised of an Analog Sense Control (ASC) die, which is built on the EE8A process technology. EE8A is a 0.35um Electrically Erasable (E2 cell based) CMOS process at Seiko Epson (SE). This process was also used by the Lattice Power Manager 2 devices (PM2) POWR1220AT8, POWR1014A AND LA-ispPAC-POWR1014A fabricated at Seiko Epson. The FPGA section of a Platform Manager 2 device is a MachXO2HC-1200 die, which is built on CS200F process technology. CS200F is a 65nm Flash CMOS process with low-k dielectric and copper metallization, fabricated by Fujitsu Limited. Both technologies going into the Platform Manager 2 product family were previously qualified and are in volume production. The combined silicon qualifications are shown below.

3.1 CS200F FPGA and EE8A PM2 & ASC Life Test Data (ELFR & HTOL)

High Temperature Operating Life (HTOL) Test

The High Temperature Operating Life test is used to thermally accelerate those wear out and failure mechanisms that would occur as a result of operating the device continuously in a system application. Consistent with JEDEC JESD22-A108 "Temperature, Bias, and Operating Life", a pattern specifically designed to exercise the maximum amount of circuitry is programmed into the device and this pattern is continuously exercised at specified voltages as described in test conditions for each device type.

HTOL Stress Conditions:

Stress Duration: 48, 168, 500, 1000 and 2000 hours

Temperature: 125°C

Stress Voltage: LPTM21, POWR1220AT8, POWR1014A and LA-ispPAC-POWR1014A: $V_{CC}= 3.47V$

Stress Voltage: MachXO2: $V_{CC}=1.3V$ (E) or $3.6V$ (C) / $V_{CCIO}=3.6V$

Method: JESD22-A108

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Table 3.1.1 CS200F and EE8A HTOL Results

Product Name	Foundry	Lot #	Qty	48 Hrs Result	168 Hrs Result	500 Hrs Result	1000 Hrs Result	2000 Hrs Result	Cumulative Hours
LPTM21	SE + FJ	Lot #1	80	N/A	0	0	0	0	160,000
LPTM21	SE +FJ	Lot #3	80	N/A	0	0	0	N/A	80,000
LA-ispPAC-POWR1014A	SE	Lot #11	77	N/A	N/A	0	N/A	N/A	38,500
LA-ispPAC-POWR1014A	SE	Lot #12	77	N/A	N/A	0	N/A	N/A	38,500
ispPAC-POWR1220AT8	SE	Lot #1	77	N/A	0	0	0	N/A	77,000
ispPAC-POWR1220AT8	SE	Lot #2	77	N/A	0	0	0	N/A	77,000
ispPAC-POWR1220AT8	SE	Lot #3	77	N/A	0	0	0	N/A	77,000
ispPAC-POWR1220AT8	SE	Lot #4	26	N/A	0	0	0	N/A	26,000
ispPAC-POWR1220AT8	SE	Lot #5	26	N/A	0	0	0	N/A	26,000
ispPAC-POWR1220AT8	SE	Lot #6	26	N/A	0	0	0	N/A	26,000
ispPAC-POWR1220AT8	SE	Lot #7	26	N/A	0	0	0	N/A	26,000
LCMXO2-1200ZE	FJ	Lot #6	60	N/A	0	0	0	N/A	60,000
LCMXO2-1200HE	FJ	Lot #6	60	N/A	0	0	0	N/A	60,000
LCMXO2-1200HC	FJ	Lot #6	60	N/A	0	0	0	N/A	60,000
LCMXO2-1200ZE	FJ	Lot #6	48	N/A	0	0	0	N/A	48,000
LCMXO2-1200HE	FJ	Lot #6	49	N/A	0	0	0	N/A	49,000
LCMXO2-1200HC	FJ	Lot #6	50	N/A	0	0	0	N/A	50,000
LCMXO2-7000ZE	FJ	Lot #1	40*	N/A	0	0	0	0	80,000
LCMXO2-7000HE	FJ	Lot #1	40*	N/A	0	0	0	0	80,000
LCMXO2-7000HC	FJ	Lot #1	40*	N/A	0	0	0	0	80,000
LCMXO2-7000ZE	FJ	Lot #1	50	N/A	0	0	0	0	100,000
LCMXO2-7000HE	FJ	Lot #1	48	N/A	0	0	0	0	96,000
LCMXO2-7000HC	FJ	Lot #1	48	N/A	0	0	0	0	96,000
LCMXO2-7000ZE	FJ	Lot #2	40*	N/A	0	0	0	0	80,000
LCMXO2-7000HE	FJ	Lot #2	40*	N/A	0	0	0	0	80,000
LCMXO2-7000HC	FJ	Lot #2	40*	N/A	0	0	0	0	80,000
LCMXO2-7000ZE	FJ	Lot #2	50	N/A	0	0	0	0	100,000
LCMXO2-7000HE	FJ	Lot #2	48	N/A	0	0	0	0	96,000
LCMXO2-7000HC	FJ	Lot #2	48	N/A	0	0	0	0	96,000

* FTG256 packaged units did not receive Flash cell pre-condition cycling prior to stress.

*EE8A Cumulative Life Testing Device Hours = 652,000
 EE8A Cumulative Result/Sample Size = 0 / 649
 EE8A FIT Rate = 18 FIT
 FIT Assumptions: CL=60%, AE=0.7eV, Tjref=55C*

*CS200F Cumulative Life Testing Device Hours = 1,631,000
 CS200F Cumulative Result/Sample Size = 0/1,019
 CS200F FIT Rate = 7 FIT
 FIT Assumptions: CL=60%, AE=0.7eV, Tjref=55C*

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Early Life Failure Rate (ELFR) Test

The Early Life Failure Rate (ELFR) evaluation is generated using the High Temperature Operating Life test conditions to verify device quality. ELFR is used to thermally accelerate those wear out and failure mechanisms that would occur as a result of operating the device continuously in a system application. Consistent with JEDEC JESD22-A108 "Temperature, Bias, and Operating Life", a pattern specifically designed to exercise the maximum amount of circuitry is programmed into the device and this pattern is continuously exercised at maximum V_{cc}/V_{ccio} .

ELFR Stress Conditions:

Stress Duration: 48 or 168 hours

Temperature: 125°C

Stress Voltage: LA-ispPAC-POWR1014A: $V_{cc}=3.6V$

Stress Voltage: MachXO2: $V_{cc}=1.26V$ (E) or 3.47V (C) / $V_{ccio}=3.47V$

Method: JESD22-A108

Table 3.1.2 CS200F and EE8A ELFR Results

Product Name	Foundry	Lot #	Qty	168 Hrs Result
ispPAC-POWR1220AT8	SE	Lot #1	796	0
ispPAC-POWR1220AT8	SE	Lot #2	800	0
ispPAC-POWR1220AT8	SE	Lot #3	799	0
LCMXO2-1200HE	FJ	Lot #6	60	0
LCMXO2-1200HC	FJ	Lot #6	60	0
LCMXO2-1200ZE	FJ	Lot #6	48	0
LCMXO2-1200HE	FJ	Lot #6	49	0
LCMXO2-1200HC	FJ	Lot #6	50	0
LCMXO2-7000ZE	FJ	Lot #1	40*	0
LCMXO2-7000HE	FJ	Lot #1	40*	0
LCMXO2-7000HC	FJ	Lot #1	40*	0
LCMXO2-7000ZE	FJ	Lot #1	50	0
LCMXO2-7000HE	FJ	Lot #1	48	0
LCMXO2-7000HC	FJ	Lot #1	48	0
LCMXO2-7000ZE	FJ	Lot #2	40*	0
LCMXO2-7000HE	FJ	Lot #2	40*	0
LCMXO2-7000HC	FJ	Lot #2	40*	0
LCMXO2-7000ZE	FJ	Lot #2	50	0
LCMXO2-7000HE	FJ	Lot #2	48	0
LCMXO2-7000HC	FJ	Lot #2	48	0

* FTG256 packaged units did not receive Flash cell pre-condition cycling prior to stress.

EE8A ELFR Cumulative Results = 0 / 2,395

CS200F ELFR Cumulative Results = 0 / 799

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3.2 CS200F FPGA and EE8A ASC – Date Code “C” Life Test Data (LTOL)

Lattice identified an unconnected node in the HVOUT charge pump circuit of the L-ASC10 and LPTM21 products. This unconnected node results in the possibility of a field reliability failure depending on the HVOUT settings, operating environment and design of the customer’s system. Based on laboratory observation and simulation results, the worst case reliability conditions are low temperature, high VCC, high HVOUT loading, and 6V HVOUT setting. A silicon fix has since been implemented to reconnect the disconnected node and mitigate the HVOUT reliability risk.

The mask change is a single-layer metal mask, considered to be a very minor layout change and was made only within the HVOUT block. Schematic and full-chip layout analysis were performed to verify that only the HVOUT block was affected and to confirm that any and all instances of the disconnected node were fixed. Mask fix validation included bench and ATE functional verification as well as reliability qualification. Production wafer sort and packaged unit testing was performed on new units prior to bench verification and reliability qualification to confirm no unintended changes were made with the new mask generation. Bench testing confirmed the correct HVOUT functionality and reliability qualification, using Low Temperature Operating Life (LTOL) stress test, confirmed that the original field reliability risk failure has been mitigated.

Low Temperature Operating Life (LTOL) Test

The Low Temperature Operating Life test is the low temperature equivalent of the High Temperature Operating Life test referenced in Section 3.1 performed to thermally accelerate the wear out and failure mechanisms that occur as a result of operating a device continuously in a system application. Consistent with JEDEC JESD22-A108 “Temperature, Bias, and Operating Life”, a pattern specifically designed to exercise the maximum amount of circuitry is programmed into the device and this pattern is continuously exercised during LTOL stress at specified voltages.

Low Temperature Operating Life (LTOL) at max datasheet analog voltage (V_{CCA}) was sufficient to qualify the mask fix. LTOL stress conditions were observed to be the worst case reliability stress for accelerating HVOUT failures. The device was configured for each HVOUT setting (6V, 8V, 10V, 12V) with worst case loading conditions for the 100uA setting (60k, 80k, 100k, 120k). The LPTM21 237fTBGA device was used as the qualification vehicle as it is a superset of the L-ASC10. Therefore, the L-ASC10 is qualified by extension.

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LTOL Stress Conditions:

Stress Duration: 168, 500, and 1000 hours

Temperature: -40°C

Stress Voltage: LPTM21, V_{CCA}= 3.6V

Stress Voltage: MachXO2, V_{CC}=3.3V

Method: JESD22-A108

Table 3.2.1 CS200F and EE8A LTOL Results

Product Name	Foundry	Lot #	Qty	168 Hrs Result	500 Hrs Result	1000 Hrs Result
LPTM21 – Date Code “C”	SE + FJ	Lot #1	160	0	0	0

Since the mask change is isolated to the HVOUT block and further manual and automated layout investigations reveal no additional connection errors, the HVOUT mask change introduces no additional reliability or functional risk to the remainder of L-ASC10 and LPTM21 circuitry. Therefore, with the addition of the specified bench verification and LTOL reliability qualification, previous silicon and package qualifications mentioned in this document are valid and sufficient for production ship release.

3.3 CS200F FPGA and EE8A PM2 & ASC NVM High Temperature Data Retention (HTRX)

High Temperature Data Retention (HTRX)

The High Temperature Data Retention test measures the reliability of Non-Volatile Memory cells while the High Temperature Operating Life test is structured to measure functional operating circuitry failure mechanisms. The ASC utilizes an Electrically Erasable (E2) NVM cell, while the FPGA utilizes a Flash NVM cell. The High Temperature Data Retention test is specifically designed to accelerate charge gain on to or charge loss off of the NVM cells in the array. Since the charge on these cells determines the actual pattern and function of the device, this test is a measure of the reliability of the device in retaining programmed information. In High Temperature Data Retention, the NVM cell reliability is determined by monitoring the cell margin after biased static operation at 150°C. All cells in all arrays are life tested in both programmed and erased states.

Data Retention (HTRX) Conditions:

Stress Duration: 168, 500, 1000 hours

Temperature: 150°C

Stress Voltage: POWR1220AT8 and LA-ispPAC-POWR1014A: $V_{CC}=3.6V$

Stress Voltage: MachXO2: $V_{CC}=1.3V$ (E) / $V_{CCIO}=3.6V$

Method: JESD22-A103/JESD22-A117

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Table 3.3.1 CS200F and EE8A High Temperature Data Retention Results

Product Name	Foundry	Lot #	Qty	168 Hrs Result	500 Hrs Result	1000 Hrs Result	Cumulative Hours
LA-ispPAC-POWR1014A	SE	Lot #11	78	0	0	NA	39,000
LA-ispPAC-POWR1014A	SE	Lot #13 ^A	39	NA	0	NA	19,500
LA-ispPAC-POWR1014A	SE	Lot #14 ^B	39	NA	0	NA	19,500
ispPAC-POWR1220AT8	SE	Lot #1	26	0	0	0	26,000
ispPAC-POWR1220AT8	SE	Lot #2	77	0	0	0	77,000
ispPAC-POWR1220AT8	SE	Lot #3	77	0	0	0	77,000
ispPAC-POWR1220AT8	SE	Lot #8 ^A	26	0	0	0	26,000
ispPAC-POWR1220AT8	SE	Lot #9 ^B	26	0	0	0	26,000
LCMXO2-1200ZE	FJ	Lot #3	76	0	0	0	76,000
LCMXO2-1200ZE	FJ	Lot #4 ^A	26	0	0	0	26,000
LCMXO2-1200ZE	FJ	Lot #4	26	0	0	0	26,000
LCMXO2-1200ZE	FJ	Lot #4 ^B	26	0	0	0	26,000
LCMXO2-1200ZE	FJ	Lot #5	80	0	0	0	80,000
LCMXO2-1200ZE	FJ	Lot #6	80	0	0	0	80,000
LCMXO2-1200ZE	FJ	Lot #6	80	0	0	0	80,000
LCMXO2-7000ZE	FJ	Lot #1	80	0	0	0	80,000
LCMXO2-7000ZE	FJ	Lot #2	80	0	0	0	80,000

A = Lot #4, #8 and #13 is a thin tunnel oxide process split.
 B = Lot #4, #9 and #14 is a thick tunnel oxide process split.

<i>EE8A Cumulative HTRX Device Hours = 310,000</i> <i>EE8A Cumulative HTRX Failure Rate = 0 / 388</i>
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<i>CS200F Cumulative HTRX Device Hours = 554,000</i> <i>CS200F Cumulative HTRX Failure Rate = 0 / 554</i>
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3.4 CS200F FPGA AND EE8A PM2 & ASC NVM Extended Endurance Cycling

Extended Endurance Cycling (ExtEnd) testing measures the durability of the Non-Volatile Memories (NVM) through program and erase cycles. Endurance testing consists of repeatedly programming and erasing all cells in the array at 25°C to simulate the programming cycles that the user would perform. This test evaluates the integrity of the tunnel oxide through which current passes to program and erase the NVM cells. The PM2/ASC utilizes an Electrically Erasable (E2) NVM cell, while the FPGA utilizes a Flash NVM cell.

NVM ExtEnd Test Conditions:

Temperature: 150°C

Stress Voltage: POWR1220AT8: $V_{CC}=3.6V$

Stress Voltage: MachXO2: $V_{CC}=1.3V (E) / V_{CCIO}=3.6V$

Method JESD22-A117A

Table 3.4.1 EE8A NVM Extended Endurance Cycling Results

Product Name	Lot #	Qty	1K CYC Result	2K CYC Result	3K CYC Result	5K CYC Result	10K CYC Result	Cumulative Cycles
POWR1220AT8	Lot #3	10	0	0	0	0	0	100,000
ispPAC-POWR1220AT8	Lot #1	10	0	NA	NA	NA	NA	10,000
ispPAC-POWR1220AT8	Lot #2	10	0	NA	NA	NA	NA	10,000
ispPAC-POWR1220AT8	Lot #3	10	0	NA	NA	NA	NA	10,000
ispPAC-POWR1220AT8	Lot #8 ^A	10	0	NA	NA	NA	NA	10,000
ispPAC-POWR1220AT8	Lot #9 ^B	10	0	NA	NA	NA	NA	10,000
ispPAC-POWR1014A	Lot #11	10	0	NA	NA	NA	NA	10,000
ispPAC-POWR1014A	Lot #13 ^A	5	0	NA	NA	NA	NA	5,000
ispPAC-POWR1014A	Lot #14 ^B	5	0	NA	NA	NA	NA	5,000

A = Lot #8 and #13 is a thin tunnel oxide process split.
B = Lot #9 and #14 is a thick tunnel oxide process split.

EE8A Cumulative Endurance Failure Rate = 0 / 80
EE8A Cumulative Endurance Cycles = 170,000

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Table 3.4.2 CS200F NVM Extended Endurance Cycling Results

Product Name	Lot #	Qty	Cycling Temp	1K CYC	10K CYC	20K CYC	50K CYC	100K CYC
LCMXO2-1200ZE	Lot #6	54	25C	0	0	0	0	0
LCMXO2-7000ZE	Lot #1	60	25C	0	0	0	0	0
LCMXO2-7000ZE	Lot #2	60	25C	0	0	0	0	0
LCMXO2-256ZE	Lot #1	30	25C	0	0	0	0	0
LCMXO2-256ZE	Lot #2	30	25C	0	0	0	0	0
LCMXO2-640ZE	Lot #1	30	25C	0	0	0	0	0
LCMXO2-2000ZE	Lot #1	30	25C	0	0	0	0	0
LCMXO2-4000ZE	Lot #1	30	25C	0	0	0	0	0

*CS200F Cumulative Endurance Failure Rate = 0 / 324
CS200F Cumulative Endurance Cycles = 32,400,000*

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3.5 Platform Manager 2 Product Family – ESD and Latch UP Data

Electrostatic Discharge-Human Body Model:

Platform Manager 2 product family was tested per the JS-001-2014 Electrostatic Discharge (ESD) Sensitivity Testing Human Body Model (HBM) procedure.

All units were tested at 25°C prior to reliability stress and after reliability stress. No failures were observed within the passing classification.

Table 3.5.1 Platform Manager 2 ESD-HBM Data

Product	48QFN	128TQFP	237ftBGA	100caBGA
Platform Manager 2	CLASS 2 on all pins except VDDD (Class 1C)			

HBM classification for Commercial/Industrial products, per JS-001-2014

All HBM levels indicated are dual-polarity (\pm)

HBM worst-case performance is the package with the smallest RLC parasitics. All other packages for a given product are qualified by similarity.

Electrostatic Discharge-Charged Device Model:

Platform Manager 2 product family was tested per the JS-002-2014, Field-Induced Charged-Device Model Test Method for Electrostatic-Discharge-Withstand Thresholds of Microelectronic Components procedure.

All units were tested at 25°C prior to reliability stress and after reliability stress. No failures were observed within the passing Classification.

Table 3.5.2 Platform Manager 2 ESD-CDM Data

Product	48QFN	128TQFP	237ftBGA	100caBGA
Platform Manager 2	CLASS 2b			

CDM classification for Commercial/Industrial products, per JS-002-2014

All CDM levels indicated are dual-polarity (\pm)

CDM worst-case performance is the package with the largest bulk capacitance. All other packages for a given product are qualified by similarity.

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Latch-Up:

Platform Manager 2 product family was tested per the JEDEC EIA/JESD78 IC Latch-up Test procedure. All Latch-up units are stressed at hot (105°C).

All units were tested at 25°C prior to reliability stress and after reliability stress. No failures were observed within the passing classification.

Table 3.5.3 Platform Manager 2 I/O Latch Up Data

Product	48QFN	128TQFP	237ftBGA	100caBGA
Platform Manager 2	>± 100mA			

I-Test LU classification for Commercial/Industrial products, per JESD78D

All IO-LU levels indicated are dual-polarity (±)

IO-LU worst-case performance is the package with access to the most IOs. All other packages for a given product are qualified by similarity.

Table 3.5.4 Platform Manager 2 Vcc Latch Up Data

Product	48QFN	128TQFP	237ftBGA	100caBGA
Platform Manager 2	>1.5x Vcc			

Vsupply Over-voltage Test LU classification for Commercial/Industrial products, per JESD78D

Vcc-LU worst-case performance is the package with access to the most individual power rails. All other packages for a given product are qualified by similarity.

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4.0 PACKAGE QUALIFICATION DATA FOR THE PLATFORM MANAGER 2 PRODUCT FAMILY

Platform Manager 2's are assembled in halogen-free packaging at Advance Semiconductor Engineering Malaysia (ASEM) in the 48-QFN (single die), the 128-TQFP (stacked-die), the 100-caBGA and 237-ftBGA (multi-chip module) package configurations.

Product Family: LPTM21, LPTM20, L-ASC10, and LPTM21L

Packages Offered: LPTM21 (237ftBGA), LPTM20 (128TQFP), L-ASC10 (48QFN), and LPTM21L (100caBGA)

4.1 Platform Manager 2 Product Family Surface Mount Preconditioning Testing

The Surface Mount Preconditioning (SMPC) Test is used to model the surface mount assembly conditions during component solder processing. All devices stressed through Temperature Cycling, Un-biased HAST and Biased HAST were preconditioned. This preconditioning is consistent with JEDEC JESD22-A113 "Preconditioning Procedures of Plastic Surface Mount Devices Prior to Reliability Testing", Moisture Sensitivity Level 3 (MSL3) package moisture sensitivity and dry-pack storage requirements.

Consistent with Lattice Semiconductor Corp. document #100164, package reliability testing can be qualified by extension. Once a package outline is qualified within a package grouping, all lower lead count (and smaller body size) packages within that package type and assembly technology are qualified by extension. Additionally, once an assembly technology has been qualified for one package type, that package type shall be qualified by extension to all future fabrication processes as long as those processes continue to use the same critical elements. Those critical elements in this case, are that the process-to-process interlayer dielectric material and thickness differences do not exceed the current production process limits for the qualification vehicle used. For 180nm and older technologies, the critical elements are considered equivalent.

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Surface Mount Preconditioning (SMPC) Stress Conditions (MSL3):

(5 Temperature Cycles between -55°C and 125°C, 24 hours bake @ 125°C, 30°C/60% RH, soak 192 hours, Reflow Simulation, 3 passes) performed before all Platform Manager 2 package tests.

Package Types: LPTM21 (237ftBGA), L-ASC10 (48QFN), and LPTM21L (100caBGA)

Method: J-STD-020 and JESD22-A113H

Table 4.1.1 Surface Mount Preconditioning Results

Product Name	Package	Wirebond	Assembly Site	Lot Number	Quantity	# of Fails	Reflow Temperature
LPTM21	237-ftBGA	Au	ASEM	Lot #1	245	0	260°C
LPTM21	237-ftBGA	Au	ASEM	Lot #2	245	0	260°C
LPTM21	237-ftBGA	Au	ASEM	Lot #3	245	0	260°C
L-ASC10	48-QFN	Au	ASEM	Lot #1	245	0	260°C
L-ASC10	48-QFN	Au	ASEM	Lot #2	245	0	260°C
L-ASC10	48-QFN	Au	ASEM	Lot #3	245	0	260°C
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #1	400	0	260°C
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #2	400	0	260°C
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #3	400	0	260°C

237-ftBGA Cumulative SMPC Failure Rate = 0 / 735
 48-QFN Cumulative SMPC Failure Rate = 0 / 735
 100-caBGA Cumulative SMPC Failure Rate = 0 / 1,200

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4.2 Platform Manager 2 Product Family High Temperature Storage Life (HTSL) Data

High Temperature Storage Life (HTSL) test is typically used to determine the effect of time and temperature, under storage conditions, for thermally activated failure mechanisms in the die and package. Units were stressed per JESD22-A103, High Temperature Storage Life. The HTSL units were stressed at 150°C. Prior to HTSL testing, all devices are subjected to Surface Mount Preconditioning.

High Temperature Storage Life (HTSL) Stress Conditions:

Stress Duration: 168, 500, 1000 hours

Temperature: 150°C

Package Types: LPTM21 (237ftBGA), L-ASC10 (48QFN), and LPTM21L (100caBGA)

Method: JESD22-A103E / JESD22-A117E

Table 4.2.1 High Temperature Storage Life Results

Product Name	Package	Wirebond	Assembly Site	Lot Number	Quantity	168 Hrs Result	500 Hrs Result	1000 Hrs Result	2000 Hrs Result	Cumulative Hours
LPTM21	237-ftBGA	Au	ASEM	Lot #1	80	0	0	0	0	160,000
LPTM21	237-ftBGA	Au	ASEM	Lot #2	80	0	0	0	0	160,000
LPTM21	237-ftBGA	Au	ASEM	Lot #3	80	0	0	0	0	160,000
L-ASC10	48-QFN	Au	ASEM	Lot #1	75	0	0	0	0	150,000
L-ASC10	48-QFN	Au	ASEM	Lot #2	75	0	0	0	0	150,000
L-ASC10	48-QFN	Au	ASEM	Lot #3	75	0	0	0	0	150,000
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #1	77		0	0	0	154,000
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #2	77		0	0	0	154,000
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #3	77		0	0	0	154,000

*Cumulative HTSL Failure Rate = 0 / 696
Cumulative HTSL Device Hours = 0 / 1,392,000*

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4.3 Platform Manager 2 Product Family Temperature Cycling (TC) Data

The Temperature Cycling test is used to accelerate those failures resulting from mechanical stresses induced by differential thermal expansion of adjacent films, layers and metallurgical interfaces in the die and package. Devices are tested at 25°C after exposure to repeated cycling between -55°C and +125°C in an air environment consistent with JEDEC JESD22-A104 “Temperature Cycling”, Condition B temperature cycling requirements. Prior to Temperature Cycling testing, all devices are subjected to Surface Mount Preconditioning.

Temperature Cycling (TC) Stress Conditions:

Stress Duration: 700 cycles

Stress Conditions: Temperature cycling between -55°C to 125°C

Package Types: LPTM21 (237ftBGA), L-ASC10 (48QFN), and LPTM21L (100caBGA)

Method: JESD22-A104E

Table 4.3.1 Temperature Cycling Results

Product Name	Package	Wirebond	Assembly Site	Lot Number	Quantity	700 Cycles Result	1400 Cycles Result
LPTM21	237-ftBGA	Au	ASEM	Lot #1	80	0	0*
LPTM21	237-ftBGA	Au	ASEM	Lot #2	80	0	0*
LPTM21	237-ftBGA	Au	ASEM	Lot #3	80	0	0*
L-ASC10	48-QFN	Au	ASEM	Lot #1	80	0	0*
L-ASC10	48-QFN	Au	ASEM	Lot #2	80	0	0*
L-ASC10	48-QFN	Au	ASEM	Lot #3	80	0	0*
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #1	77	0	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #2	77	0	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #3	77	0	0

*2x Readout quantity = 75 units/lot

Cumulative Temp Cycle Failure Rate = 0 / 711

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4.4 Platform Manager 2 Product Family Unbiased HAST (UHAST) Data

Unbiased Highly Accelerated Stress Test (HAST) testing uses both pressure and temperature to accelerate penetration of moisture into the package and to the die surface. The Unbiased HAST test is designed to detect ionic contaminants present within the package or on the die surface, which can cause chemical corrosion. Consistent with JEDEC JESD22-A118, “Accelerated Moisture Resistance – Unbiased HAST,” the Unbiased HAST conditions are either 96-hour exposure at 130°C, 85% RH, or 264-hour exposure at 110°C, 85% RH. Prior to Unbiased-HAST testing, all devices are subjected to Surface Mount Preconditioning.

Unbiased HAST (UHAST) Stress Conditions:

Stress Duration: 264h (BGA)

Chamber Conditions: 110°C, 15psig, 85% RH (BGA)

Package Types: LPTM21L (100caBGA)

Method: JESD22-A101D

Table 4.4.1 Unbiased HAST Results

Product Name	Package	Wirebond	Assembly Site	Lot Number	Quantity	264 Hrs Result
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #1	77	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #2	77	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #3	77	0

Cumulative Unbiased HAST failure Rate = 0 / 231

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4.5 Platform Manager 2 Product Family Biased HAST (BHAST) Data

Biased Highly Accelerated Stress Test (BHAST) testing uses both pressure and temperature to accelerate penetration of moisture into the package and to the die surface. The Biased HAST test is used to accelerate threshold shifts in the MOS device associated with moisture diffusion into the gate oxide region as well as electrochemical corrosion mechanisms within the device package. Consistent with JEDEC JESD A110-B “Highly-Accelerated Temperature and Humidity Stress Test (HAST)”, the biased HAST conditions are with Vcc bias and alternate pin biasing in an ambient of 110°C, 85% RH, and 2 atmospheres of pressure. Prior to Biased HAST testing, all devices are subjected to Surface Mount Preconditioning.

Biased HAST (BHAST) Stress Conditions:

Stress Duration: 96 hours (QFN), 264h (BGA)

Stress Voltage: Vcc = 3.6V; LPTM21L: Vcc=3.47V, Vccio=3.47V, Vvdc=13.2V

Chamber Conditions: 130°C, 15psig, 85% RH (QFN) / 110°C, 15psig, 85% RH (BGA)

Package Types: LPTM21 (237ftBGA), L-ASC10 (48QFN), and LPTM21L (100caBGA)

Method: JESD22-A101D

Table 4.5.1 Biased HAST Results

Product Name	Package	Wirebond	Assembly Site	Lot Number	Quantity	264 Hrs Result
LPTM21	237-ftBGA	Au	ASEM	Lot #1	80	0
LPTM21	237-ftBGA	Au	ASEM	Lot #2	80	0
LPTM21	237-ftBGA	Au	ASEM	Lot #3	80	0
L-ASC10	48-QFN	Au	ASEM	Lot #1	80	0
L-ASC10	48-QFN	Au	ASEM	Lot #2	80	0
L-ASC10	48-QFN	Au	ASEM	Lot #3	80	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #1	77	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #2	77	0
LPTM21L	100-caBGA	AuPCC	ASEM	Lot #3	77	0

Cumulative Biased HAST failure Rate = 0 / 711

5.0 WAFER FAB PROCESS RELIABILITY

The Platform Manager 2 product family is a two-die solution, in both stacked die TQFP and multi-chip module ftBGA package configurations and is built on two wafer fab technologies. The PM2/ASC die is built on the EE8A process technology. EE8A is a 0.35um Electrically Erasable (E2 cell based) CMOS process at Seiko Epson (SE). The FPGA die is built on CS200F (also known as EE12) process technology. CS200F is a 65nm Flash CMOS process with low-k dielectric and copper metallization, fabricated by Fujitsu Limited. Platform Manager 2 end-of-life is a combination of Wafer Level Reliability (WLR) from both fabs.

5.1 EE8A Process Reliability Wafer Level Review

Several key fabrication process related parameters have been identified by the foundry that would affect the Reliability of the End-Product. These parameters are tested during the Development Phase of the Technology. Passing data (a 10yr lifetime at the reliability junction temperature) must be obtained for three lots minimum for each parameter before release to production. Normal operating conditions are defined in the Electrical Design Rules (EDR). These parameters are:

Hot Carrier Immunity (HCI): Effect is a reduction in transistor I_{dsat} . Worst case is low temperature.

Time Dependent Dielectric Breakdown (TDDB): Transistor and capacitor oxide shorts or leakage.

Negative Bias Temperature Instability (NBTI): Symptom is a shift in V_{th} (also a reduction in I_{dsat}).

Electromigration Lifetime (EML): Symptom is opens within, or shorts between, metal conductors.

Stress Migration (SM): Symptom is a void (open) in a metal Via due to microvoid coalescence. SM is not an issue for the EE8A BEOL (etched Al lines, W plug Vias, SiO IMD).

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Table 5.1.1 Wafer Level Reliability Results for EE8A (0.35 um) Process Technology

Hot Carrier Immunity (HCI)

Device	LVN	LVP
deltalds	-10%	-10%
Celsius	25	25
Vgstress	Vd/2	0
Vds	3.6	-3.6
DC-HCI TTF >1yr	3 lots ≥ 5.5yr	2 lots ≥ 8.2e3yr

Time Dependent Dielectric Breakdown (TDDB)

Device	LVN	MIM
Celsius	130	130
Vg	3.3	15
Area	8000um ²	2.25e4um ²
0.1% TTF	3 lots ≥ 2.8e3yr	3 lots ≥ 2.1e3yr

Electromigration Lifetime (EML)

Layer	M1	M2	M3
Celsius	130	130	130
Delta R	+20%	+20%	+20%
Jmax	1.0mA/um	1.4mA/um	1.4mA/um
0.1% TTF	3 lots ≥ 22.4yr	3 lots ≥ 30.5yr	3 lots ≥ 16.2yr

Note: Reliability life times are based on listed temperature and used conditions. Detailed WLR test conditions are available upon request.

5.2 CS200F Process Reliability Wafer Level Review

Several key fabrication process related parameters have been identified by the foundry that would affect the Reliability of the End-Product. These parameters are tested during the Development Phase of the Technology. Passing data (a 10yr lifetime at the reliability junction temperature) must be obtained for three lots minimum for each parameter before release to production. Normal operating conditions are defined in the Electrical Design Rules (EDR). These parameters are:

Hot Carrier Immunity (HCI): Effect is a reduction in transistor I_{dsat} . Worst case is low temperature.

Time Dependent Dielectric Breakdown (TDDB): Transistor and capacitor oxide shorts or leakage.

Negative Bias Temperature Instability (NBTI): Symptom is a shift in V_{th} (also a reduction in I_{dsat}).

Electromigration Lifetime (EML): Symptom is opens within, or shorts between, metal conductors.

Stress Migration (SM): Symptom is a void (open) in a metal Via due to microvoid coalescence.

Table 5.2.1 Wafer Level Reliability Results for CS200F (65nm) Process Technology

Hot Carrier Immunity @25°C

Device	LVN	LVP	MVN	MVP	HVN	HVP
delta I_{ds}	-10%	-10%	-10%	-10%	-10%	-10%
Vgstress	Vd/2	Vd	Vd/2	Vd	Vd/2	Vd
Vds	1.26	-1.26	3.465	-3.465	5.25	-5.25
TTF	3 lots>34 yr DC	3 lots>71 yr DC	3 lots>20 yr AC*	3 lots>680 yr DC	3 lots>3.5e6s DC**	3 lots>1e9 s DC

Time Dependent Dielectric Breakdown @100°C

Device	LVN	LVP	MVN	MVN Accum	MVP	Intermed. IMD	Semi-Global IMD
Vg	1.26	-1.26	3.465	3.465	-3.465	3.465	3.465
Max Area	2.2 cm ²	22 cm ²	1 cm ²	1 cm ²	2.5 cm ²	L/S=100nm	L/S=200nm
0.1% TTF	3 lots>2.5e5 yr	3 lots>1.4e3 yr	3 lots>25 yr	3 lots>42 yr	3 lots>390 yr	3 lots>230 yr	3 lots>6600 yr

Device	HVN	HVN	HVN	HVN Accum	HVN Accum	HVN Accum
Vg	5.5	6.75	8.8	5.5	6.75	8.8
Max Area	5e-4 cm ²	2e-4 cm ²	2e-4 cm ²	5e-4 cm ²	2e-4 cm ²	2e-4 cm ²
0.1% TTF	3 lots>1.3e3 yr	3 lots>134 yr	3 lots>2.3e4 hr***	3 lots>1.2e3 yr	3 lots>128 yr	3 lots>2.3e4 hr***

Device	HVP	HVP	HVP	HVP Accum	HVP Accum	HVP Accum
Vg	-5.5	-6.75	-8.8	-5.5	-6.75	-8.8
Max Area	5e-4 cm ²	2e-4 cm ²	2e-4 cm ²	5e-4 cm ²	2e-4 cm ²	2e-4 cm ²
0.1% TTF	3 lots>230 yr	3 lots>167 yr	3 lots>9.5e3 hrs***	3 lots>20 yr	3 lots>17 yr	3 lots>1310 hrs***

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Negative Bias Temperature Instability (NBTI) @100°C

Device	LVP	MVP
delta Vth	50mv	100mv
Vg	-1.26	-3.465
TTF	3 lots>5.8e5 yr	3 lots>4.2e3 yr

Device	LVP	MVP
delta Ids	10%	10%
Vg	-1.26	-3.465
TTF	3 lots>1.9e4 yr	3 lots>9.9e5 yr

Electromigration Lifetime (EML) @100°C

Device	Intermediate	Semi-Global	Global	Top AI
delta R	+5%	+5%	+5%	+5%
Jmax	6.65E+05	6.65E+05	6.65E+05	2.85E+05
0.1% TTF	3 lots>380 yr	3 lots>77 yr	3 lots>22 yr	3 lots>71 yr

Stress Migration (SM) @100°C

Device	Intermediate	Semi-Global	Global
delta R	+100%	+100%	+100%
TTF	3 lots>2400 yr	3 lots>328 yr	3 lots>1.1e4 yr

All time-to-fail (TTF) data rounded to 2 significant digits.

* AC corresponds to 2% Isub duty cycle for inverter which is factor of 50 times DC TTF

** Maximum FLASH Memory Reads are limited to 7.5E13 cycles over the lifetime of the product.

*** 8.8V Vpp TTF is minimum 150 hrs

Note: Reliability life times are based on listed temperature and used conditions. Detailed WLR test conditions are available upon request.

6.0 PLATFORM MANAGER 2 ADDITIONAL FAMILY DATA

Table 6.01 Package Assembly Data

Package Attributes / Assembly Sites	ASEM			
Die Family (Product Line)	L-ASC10	LPTM20	LPTM21	LPTM21L
		ASC (L-ASC10) + FPGA (MXO2-1200HC)		
Wafer Fabrication Process	EE8A	EE8A & CS200F		
+Package Assembly Site	Malaysia			
Package Type	QFN	TQFP	ftBGA	caBGA
Die Configuration	Single Die	Stacked Die	Multi-Chip Module	
Pin Count	48	128	237	100
Die Preparation/Singulation	wafer saw, full cut			wafer saw, step cut
Die Attach Material	CRM1076DS	FH900 + Si Spacer	Ablestik 2100A	Ablestik 2100A
Mold Compound	CEL-9240HF10AK	CEL-9510HFL-U	G750E	G750SE
Wire Bond Material	Gold (Au) (2N)			AuPCC (CuPdAu)
Wire Bond Diameter	0.8mil bondwire	0.7mil Au bondwire	0.8mil bondwire	
Wire Bond Methods	Thermosonic Ball			
Lead frame or Substrate Material	C194	A07881-0	Green, AUS308, CL832NX	Green, AUS308, HL832NX(A-EX)
Lead Finish or Solder Balls	100% Sn	Matte Sn (annealed)	SAC 305	
Marking	Laser			

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7.0 REVISION HISTORY

Table 7.0.1 Platform Manager 2 Product Family Qualification Summary Revisions

Date	Revision	Request	Section	Change Summary
April 2014	A		---	New release
October 2014	B			PTM21-237ftBGA update; remove Jedec revision level from Table 2.2; update Qual Flow chart
April 2018	C		3	Silicon Qualification update; Added Section 3.2 CS200F FPGA and EE8A ASC – Date Code “C” Life Test Data (LTOL)
May 2018	D			Added 1000hr LTOL table entry
February 2019	E			Added LPTM21L 100caBGA qualification results
December 2019	F			Fix FIT typo in Section 2. Update Table 3.1.1 and 3.3.1.

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